CLAIMS

WHAT IS CLAIMED IS:

1. A sputtering target, having a composition formula expressed as $Fe_{100-a-b-c}$-Cu_a-Si_b-M_c in terms of atomic ratio, wherein $0.1 \leqq a \leqq 5.0$, $10.0 \leqq b \leqq 20.0$, $10.0 \leqq c \leqq 25.0$, and M is one or more elements selected from Nb and B, containing a remainder composed of unavoidable impurities, and having a bending strength of 500 MPa or more.

2. The sputtering target according to claim 1, wherein a number of Fe phases having an inscribed circle diameter of 1 μm or greater is less than 1.0 per 60000 μm^2.

3. A method for manufacturing a sputtering target, comprising:

vacuum-melting a molten alloy for producing a powder, wherein the powder is produced by a gas atomization method using an Ar gas;

removing coarse powder by classification from the powder to obtain a raw material powder; and

pressure-sintering the raw material powder, wherein the molten alloy has a composition formula expressed as $Fe_{100-a-b-c}$-Cu_a-Si_b-M_c in terms of atomic ratio, wherein $0.1 \leqq a \leqq 5.0$, $10.0 \leqq b \leqq 20.0$, $10.0 \leqq c \leqq 25.0$, and M is one or more elements selected from Nb and B, and contains a remainder composed of unavoidable impurities.